



## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of	) Confirmation No. 4499
Inventor(s): Li Yao et al.	) ) Group Art Unit: 1792 ) ) Examiner: ALANKO, A. K. ) ) )
Appln. No.: 10/689,043	
Filed: October 21, 2003  For: Abrasive-Free Chemical mechanical polishing composition and polishing process containing same	

## RESPONSE UNDER 37 C.F.R. §1.116

U.S. Patent and Trademark Office Randolph Building 401 Dulany Street Alexandria, Virginia 22314 MAIL STOP – AMENDMENT

Sir:

In response to the Final Office Action mailed on June 16, 2008, the time for responding to which extends up to October 16, 2008, with payment of one month extension fees, please amend the above application as follows:

Amendment to the claims begins on page 2 of this paper; and Remarks begin on page 6 of this paper.